ABSTRACT

An object of the present invention is to eliminate drawbacks of conventional multi-layered antireflection films, that is, that a lot of time is required in the formation of a transparent conductive thin film and a low-refractive index layer leading to low processing speed, the corrosion resistance of the transparent conductive thin film is unsatisfactory, and the reflectance over the whole visible light region is not constant. This object can be attained by adopting a structure comprising: a transparent layer 3, with a pencil hardness of H or more, formed of a cured product of an ionizing radiation-curable resin composition; provided on one side of the transparent layer 3, a concave-convex portion 2 comprising innumerable fine concaves and convexes provided at a pitch of not more than the wavelength of light; a transparent substrate film 1 optionally provided on the transparent layer 3 on its side remote from the concave-convex portion 2; and a cover layer, having a lower refractive index than the transparent layer, preferably provided on the fine concaves and convexes.